

ABSTRACT OF THE DISCLOSURE

A vacuum arc vapor deposition apparatus can form a film of good quality without uselessly increasing a time from start of film deposition to completion thereof even when a trigger electrode induces vacuum arc discharge in response to turn-off of the vacuum arc discharge during deposition of the film onto the deposition target object. For example, the vacuum arc vapor deposition apparatus includes a shield member moved to and away from a position between a vapor source and a holder for supporting the deposition target object, a drive device for locating the shield plate selectively in a shield position between the vapor source and the holder, and a retracted position shifted from the shield position, a detector (e.g., current detector) detecting turn-on/off of the vacuum arc discharge, and a control portion controlling the drive device to locate the shield plate in the shield position when the detector detects turn-off of the vacuum arc discharge, and to locate the shield plate in the retracted position when a time required for stabilizing the vacuum arc discharge elapses after the detector detected turn-on of the vacuum arc discharge.